

FIG. 1

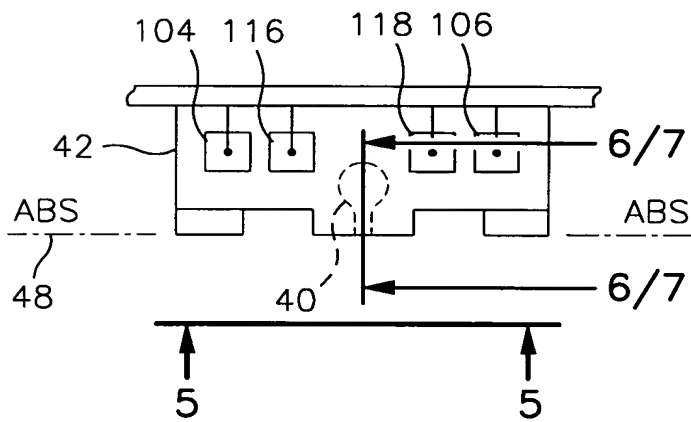


FIG. 2

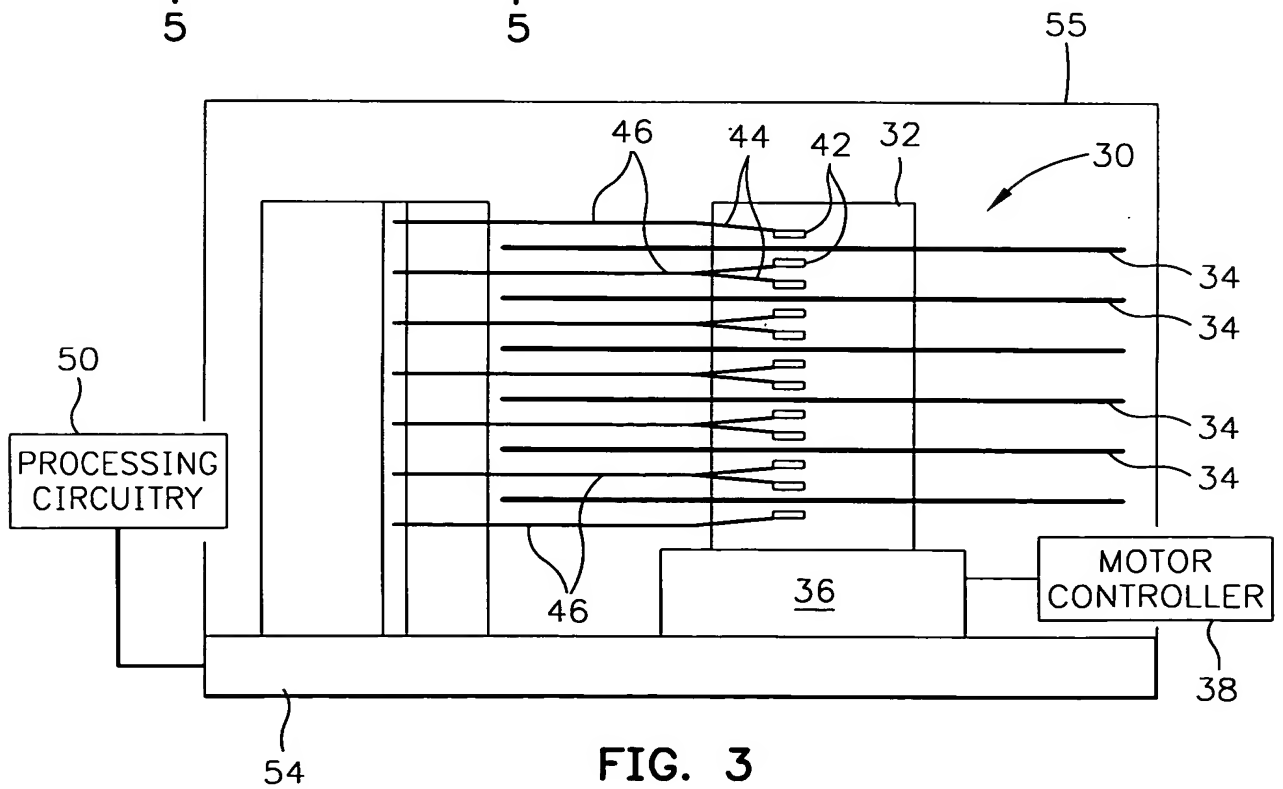
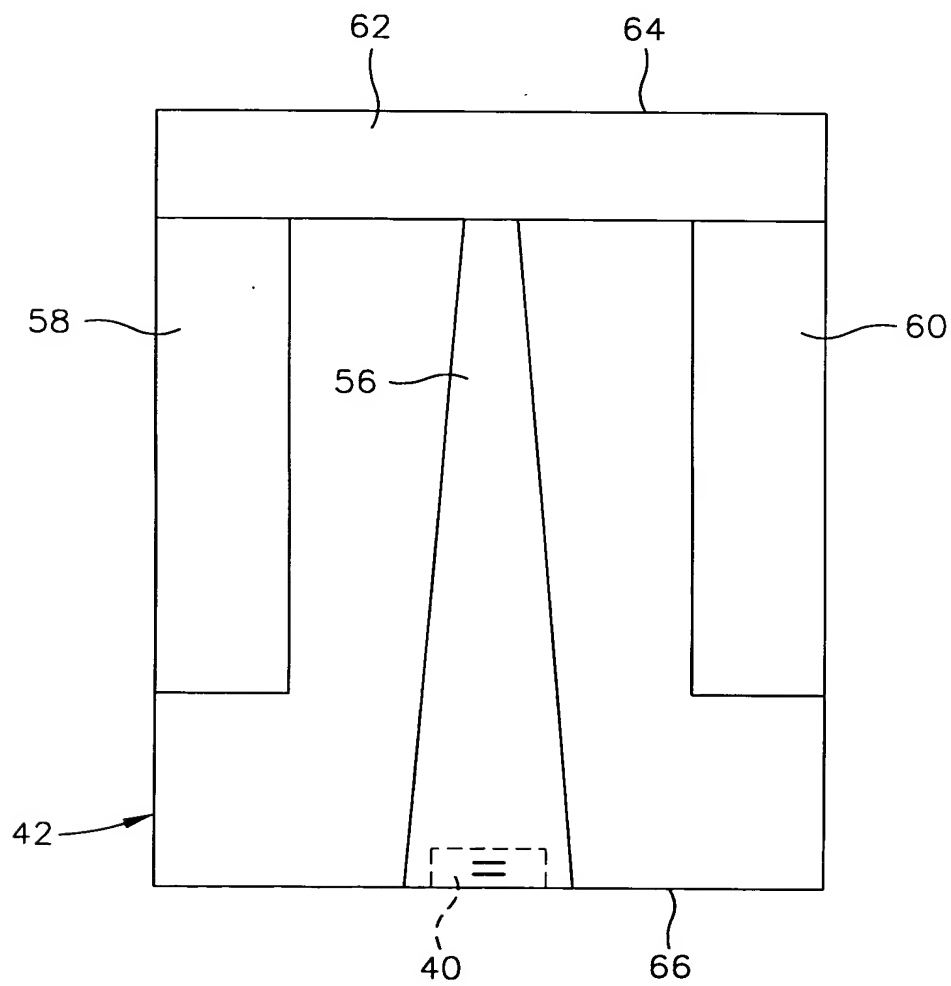
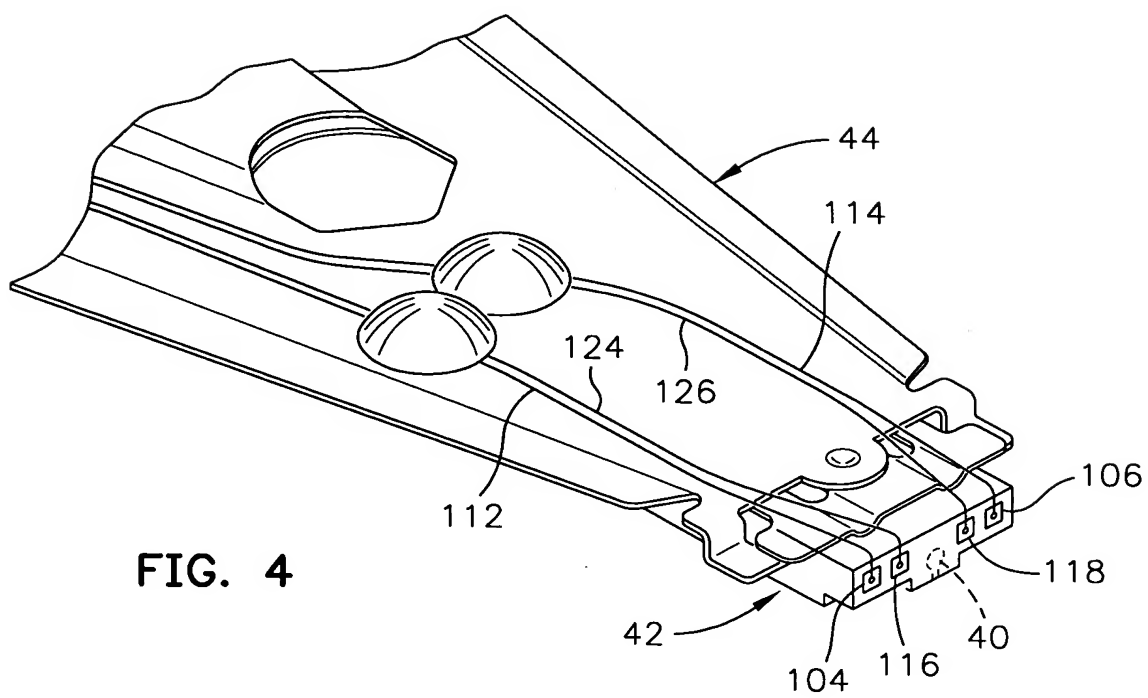
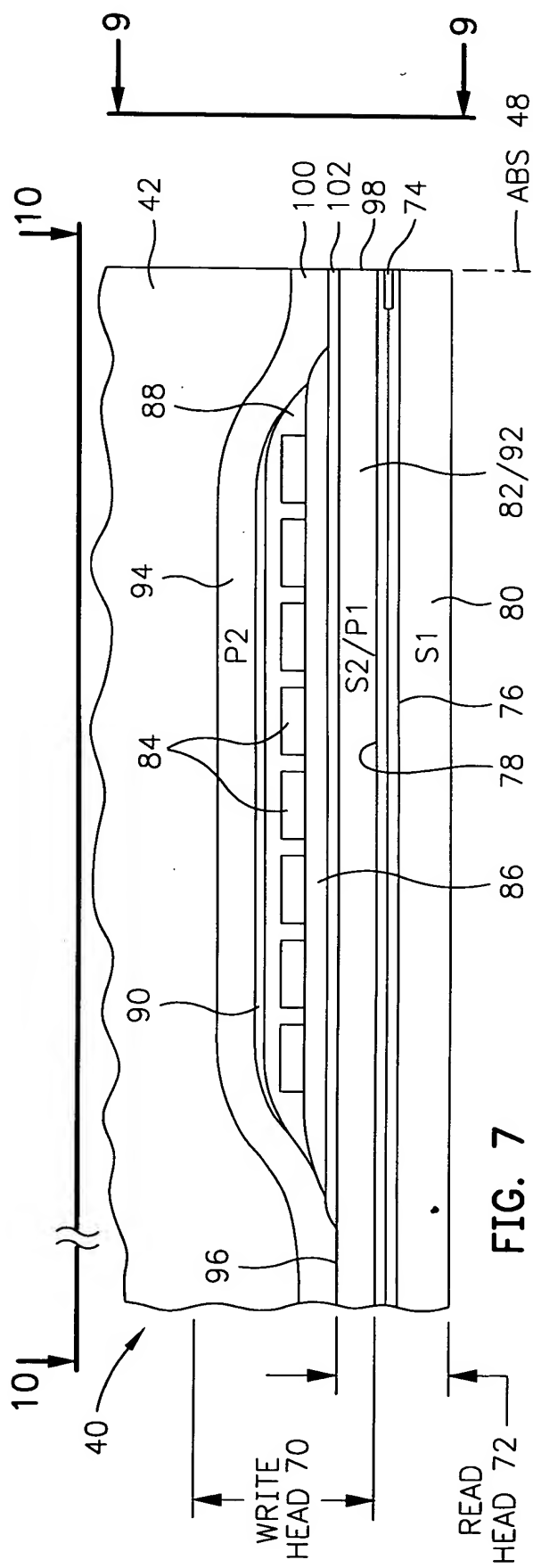
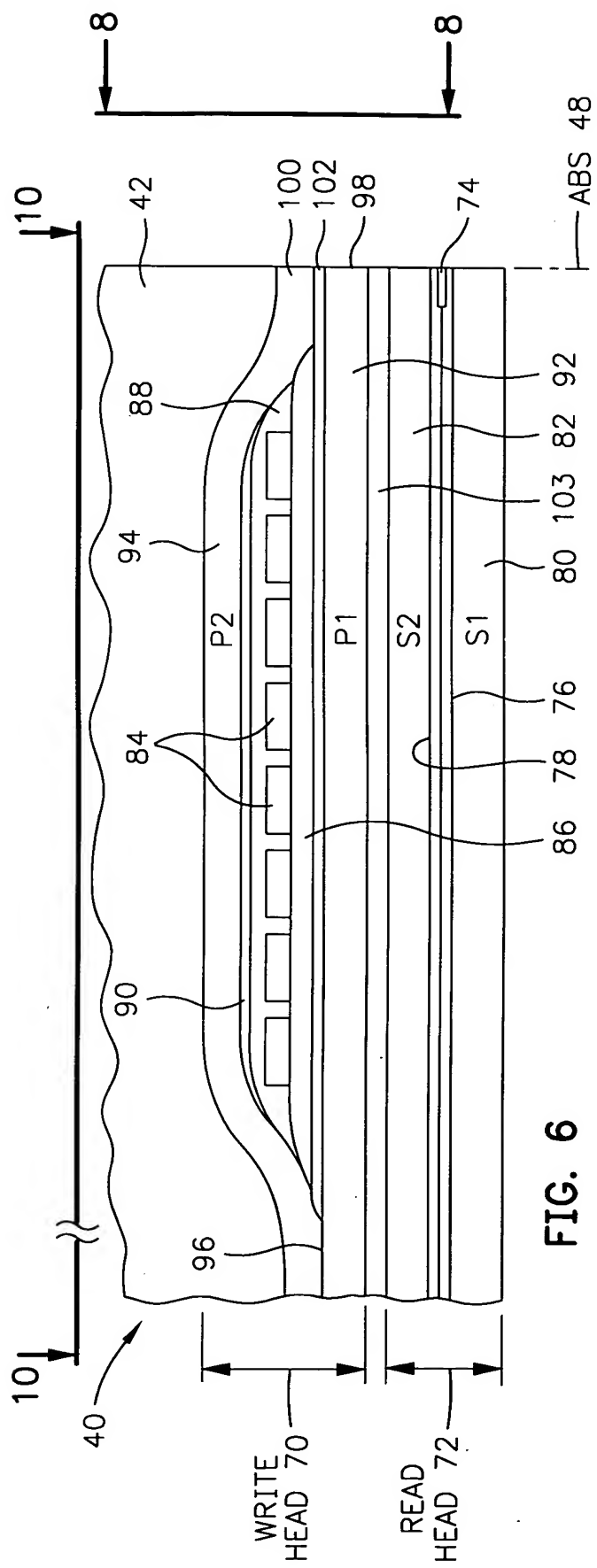


FIG. 3





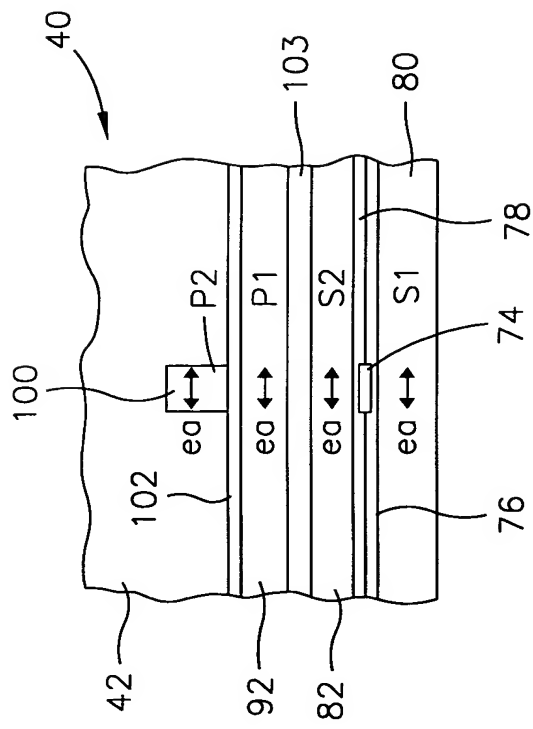


FIG. 8

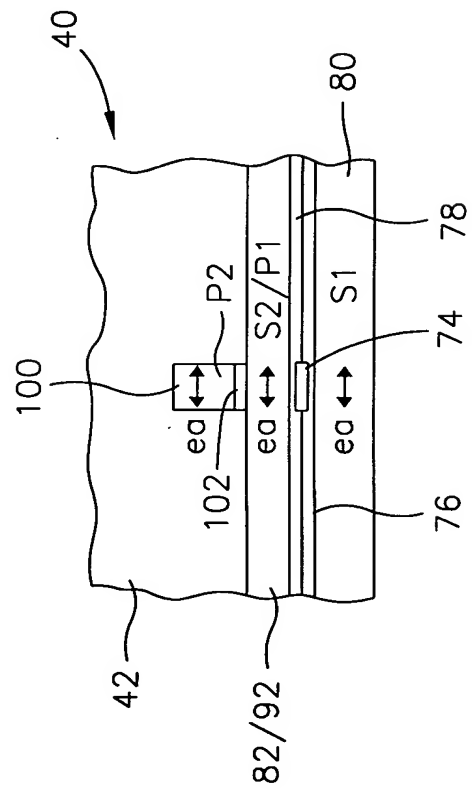


FIG. 9

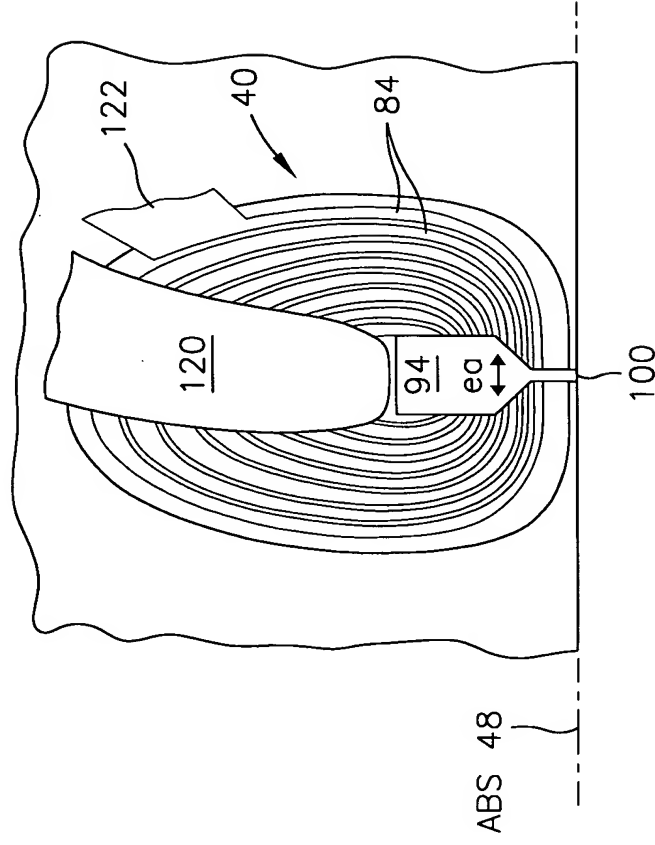


FIG. 10

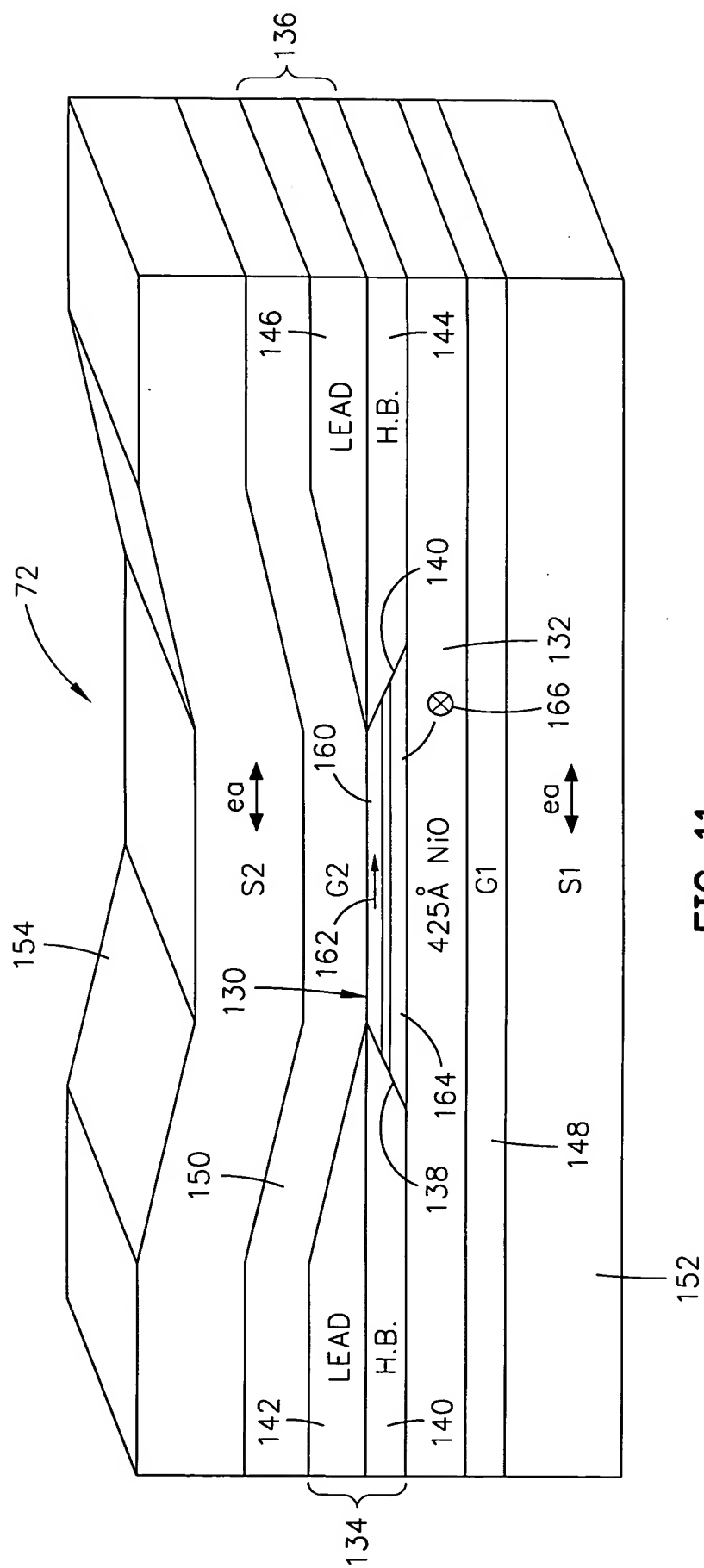


FIG. 11
(ABS)

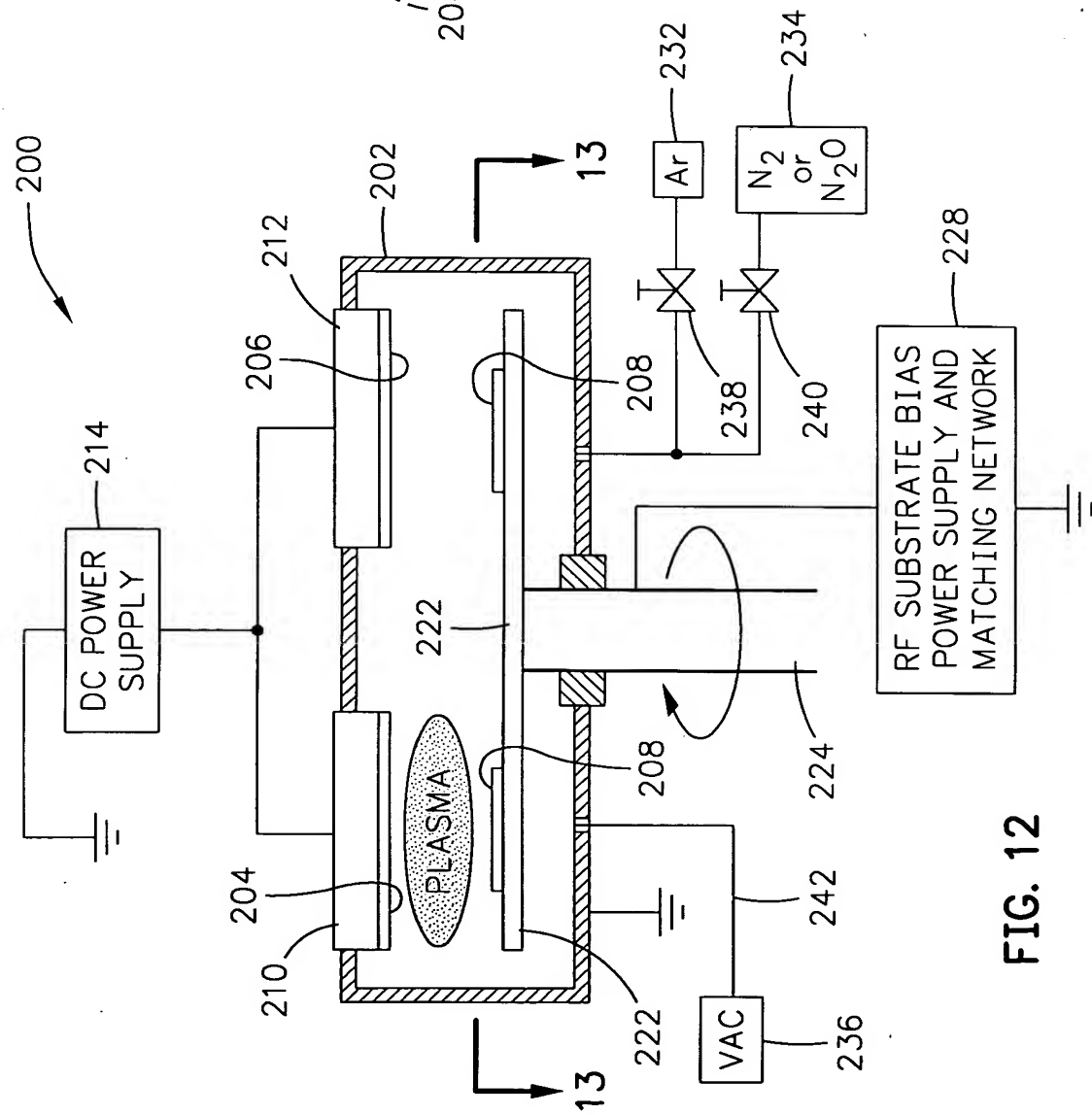


FIG. 12

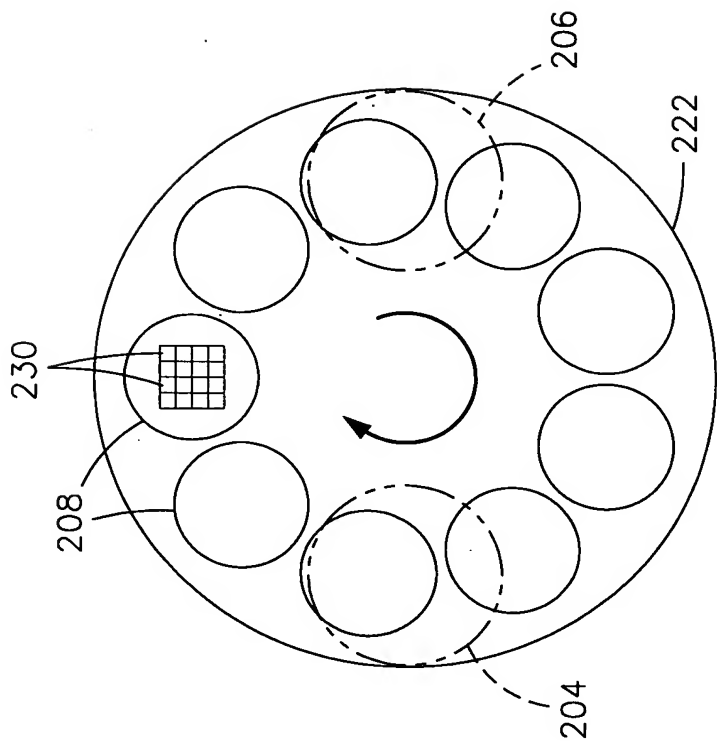


FIG. 13

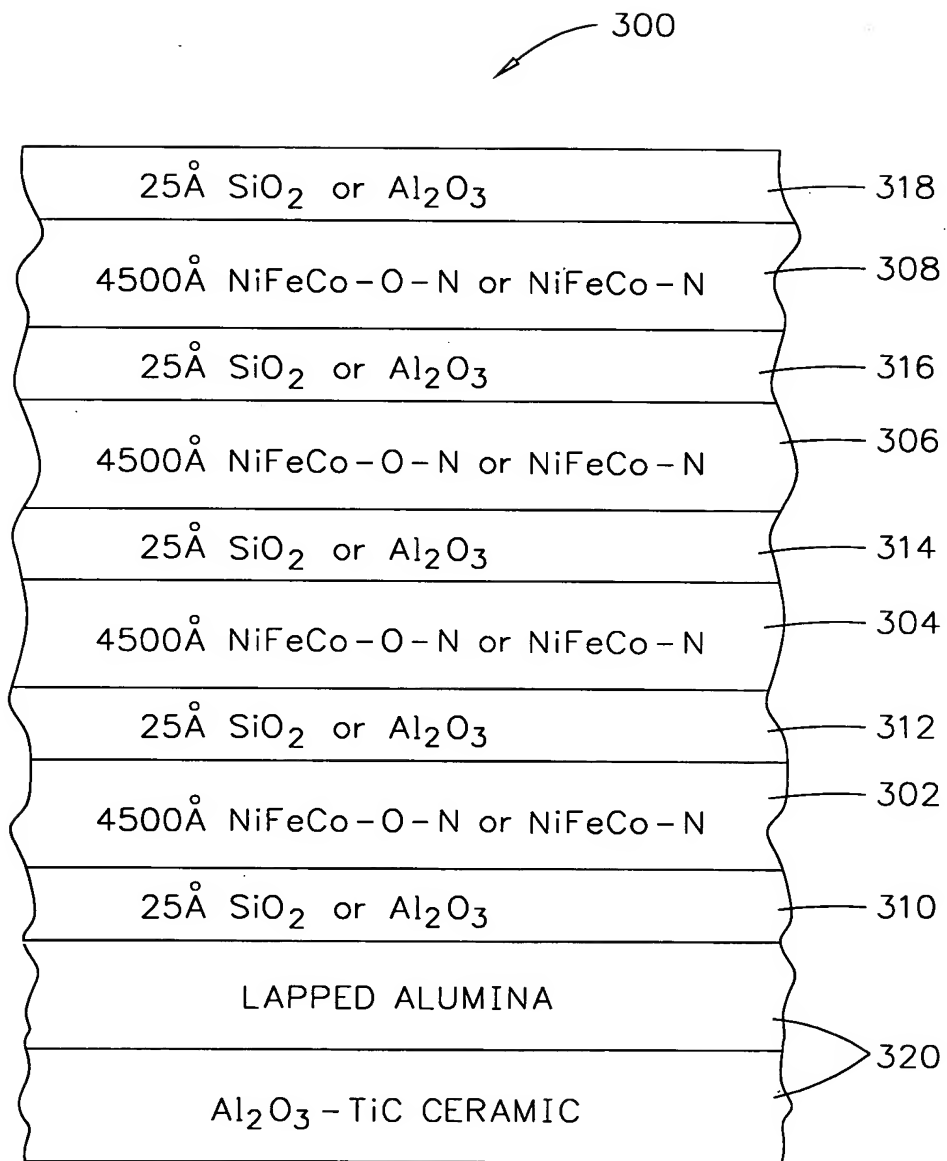
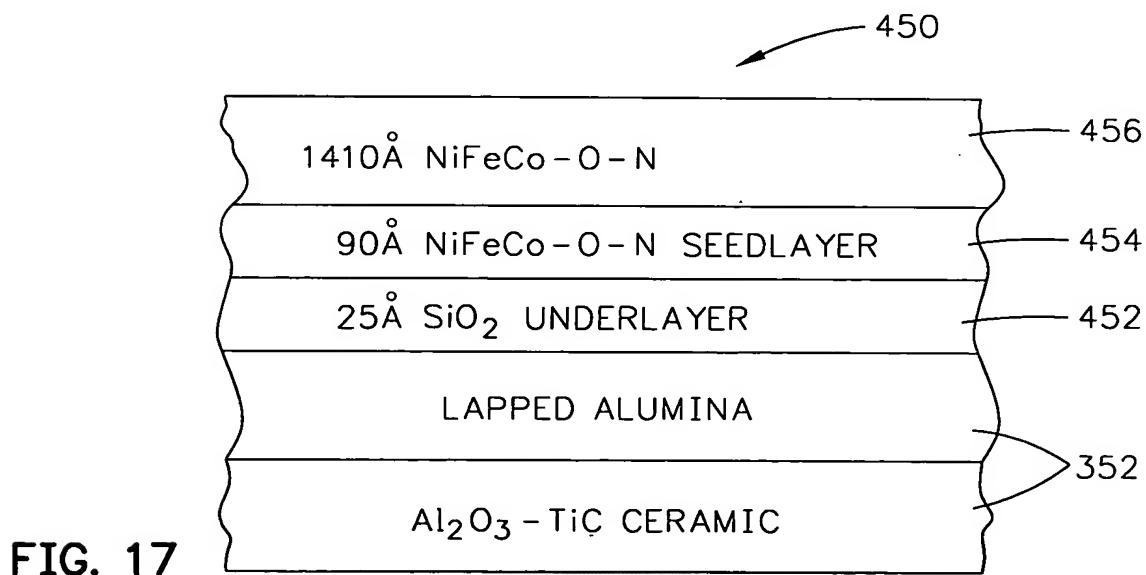
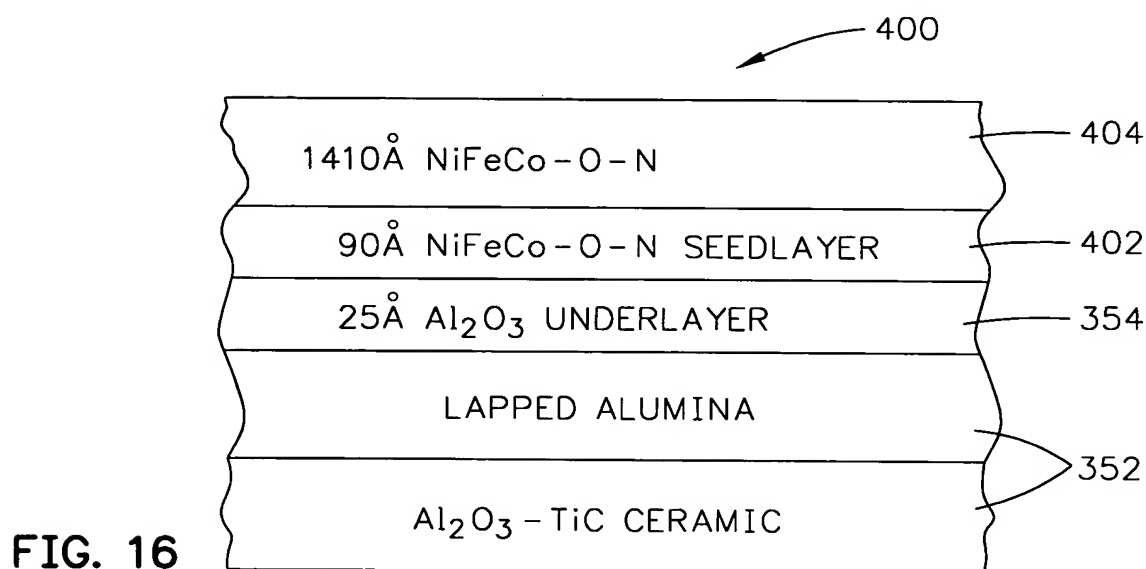
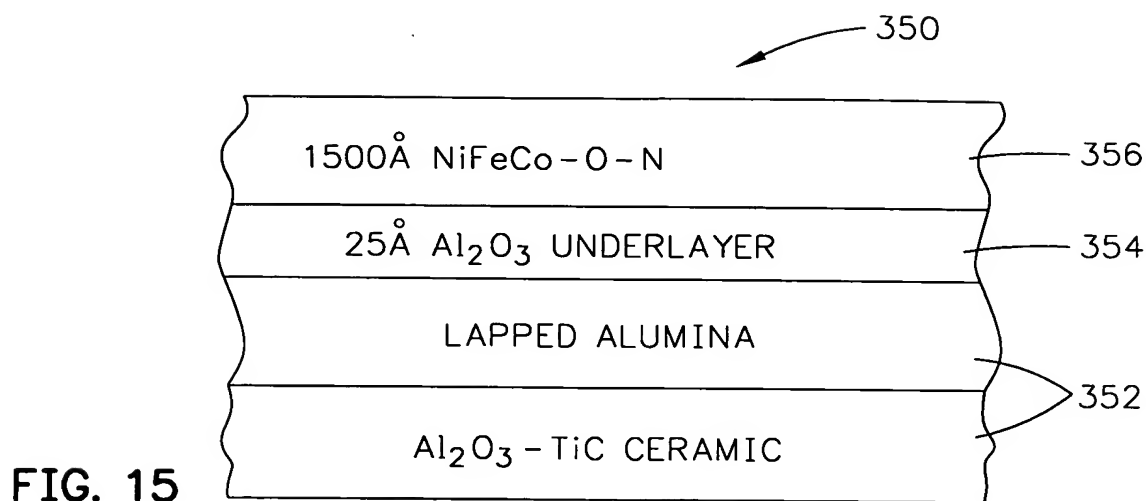
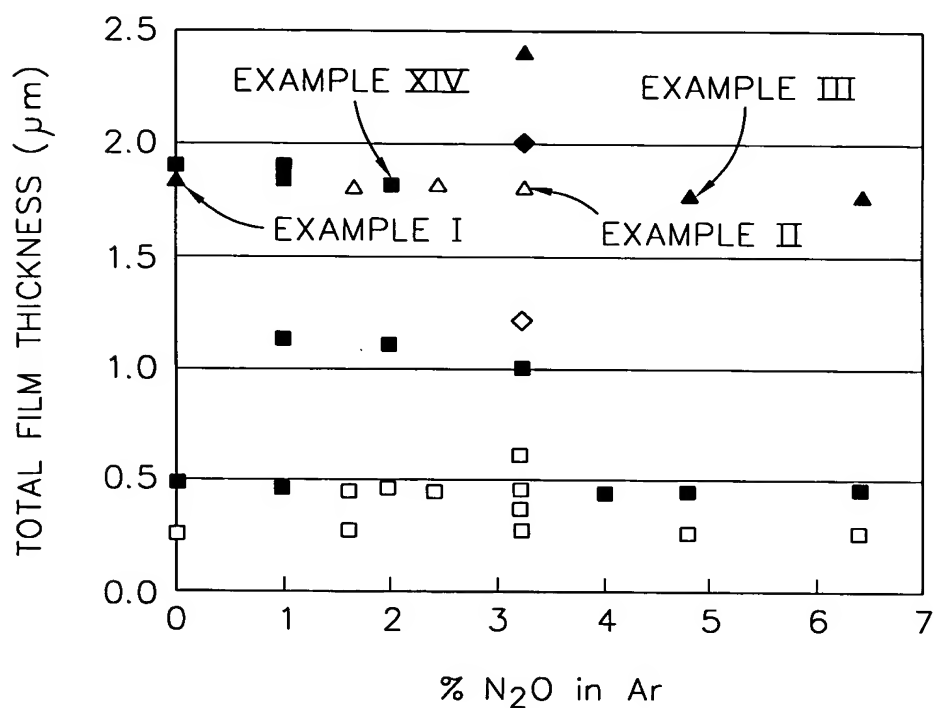


FIG. 14



THICKNESS AND N₂O CONCENTRATION
DEPENDENCE OF IN-PLANE AND VERTICAL H_k IN
SINGLE LAYER AND LAMINATED NiFeCo-O-N FILMS
(DC MAG 1750 W, 2.0X10⁻³ mbar, NO BIAS)



- SINGLE LAYER FILMS - IN PLANE H_k
- ◇ 2X LAMINATED FILMS - IN PLANE H_k
- △ 4X LAMINATED FILMS - IN PLANE H_k
- SINGLE LAYER FILMS - VERTICAL H_k
- ◆ 2X LAMINATED FILMS - VERTICAL H_k
- ▲ 4X LAMINATED FILMS - VERTICAL H_k

FIG. 18

THICKNESS AND N₂ CONCENTRATION
DEPENDENCE OF IN-PLANE AND VERTICAL H_k IN
SINGLE LAYER AND LAMINATED NiFeCo-N FILMS
(DC MAG 1750 W, 2.0X10⁻³ mbar, NO BIAS)

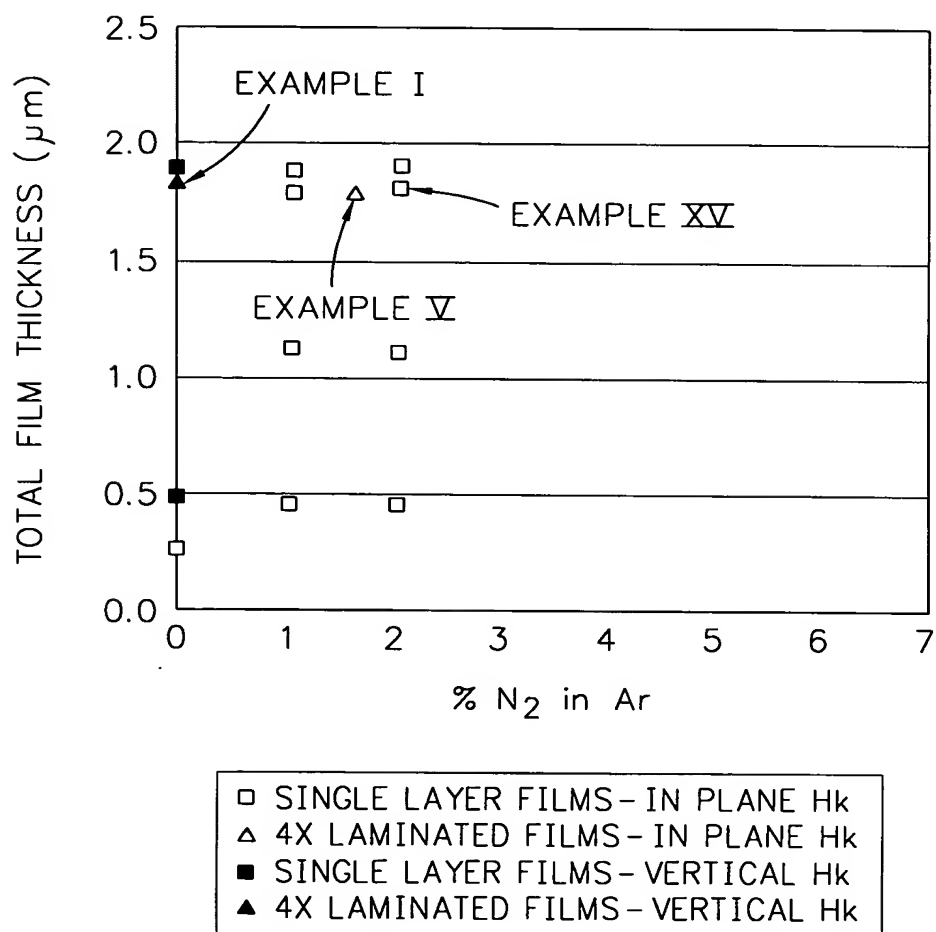


FIG. 19

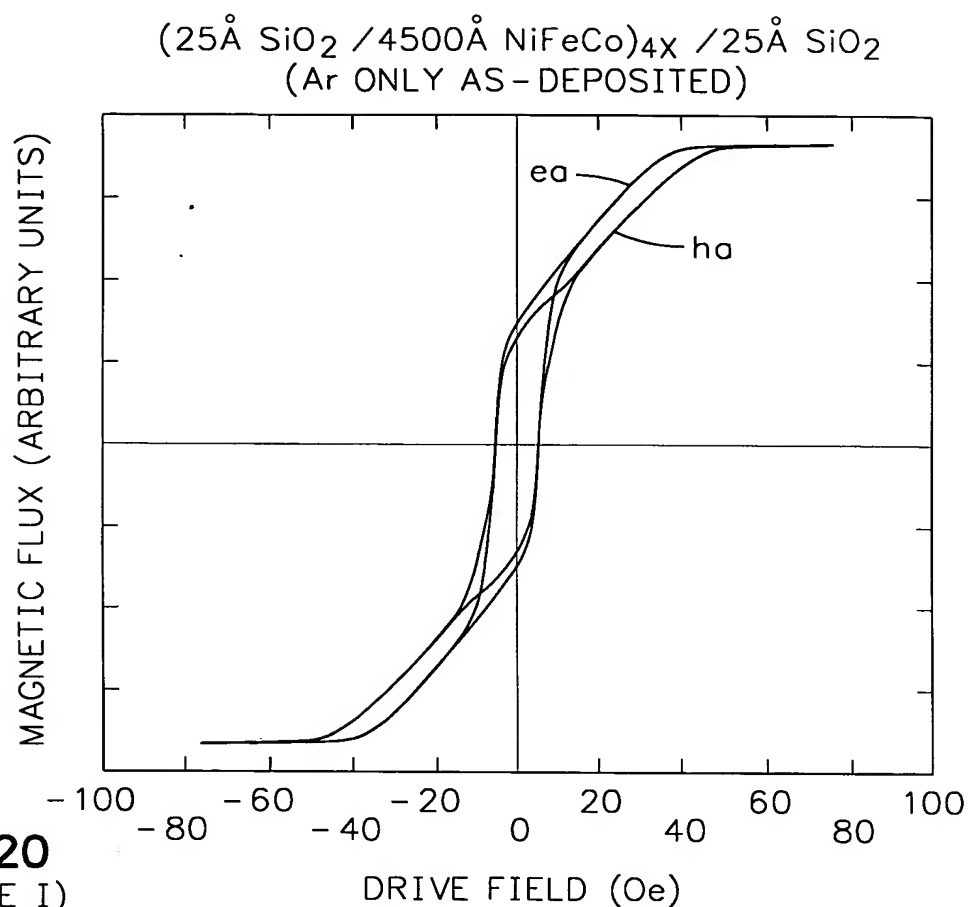


FIG. 20
(EXAMPLE I)

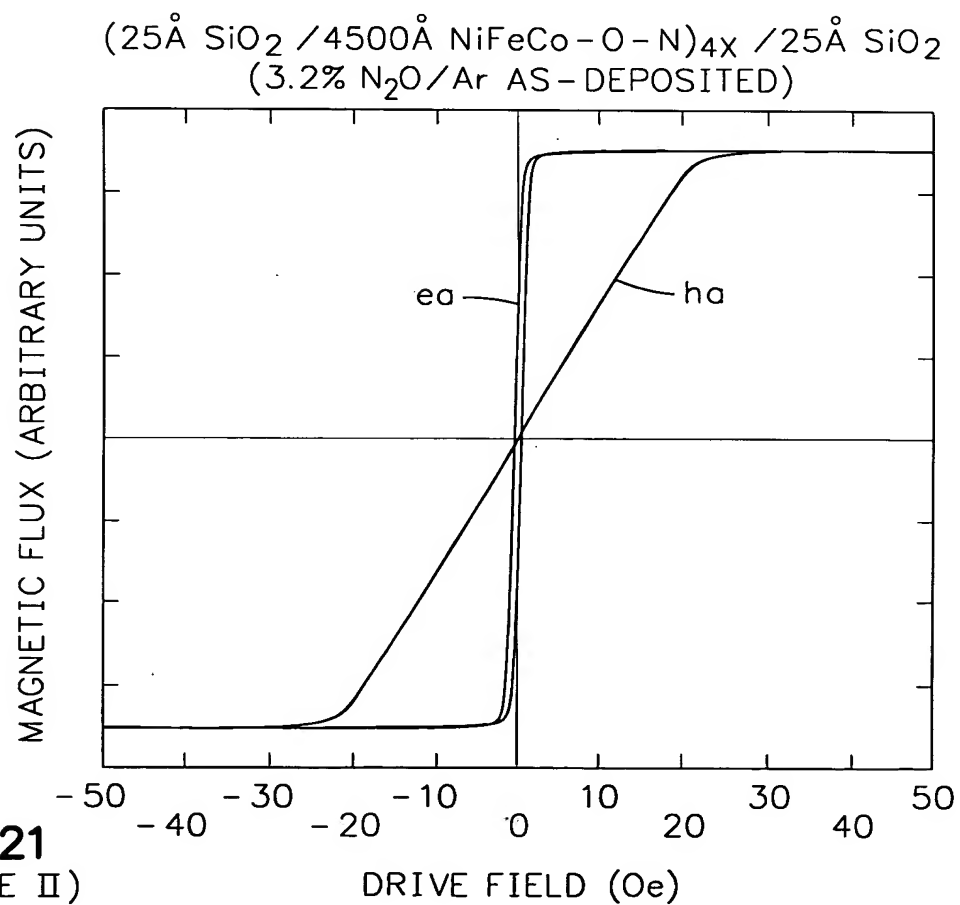


FIG. 21
(EXAMPLE II)

(18Å ALUMINA/4500Å NiFeCo-N)₄X / 25Å ALUMINA
(1.6% N₂ /Ar AS-DEPOSITED)

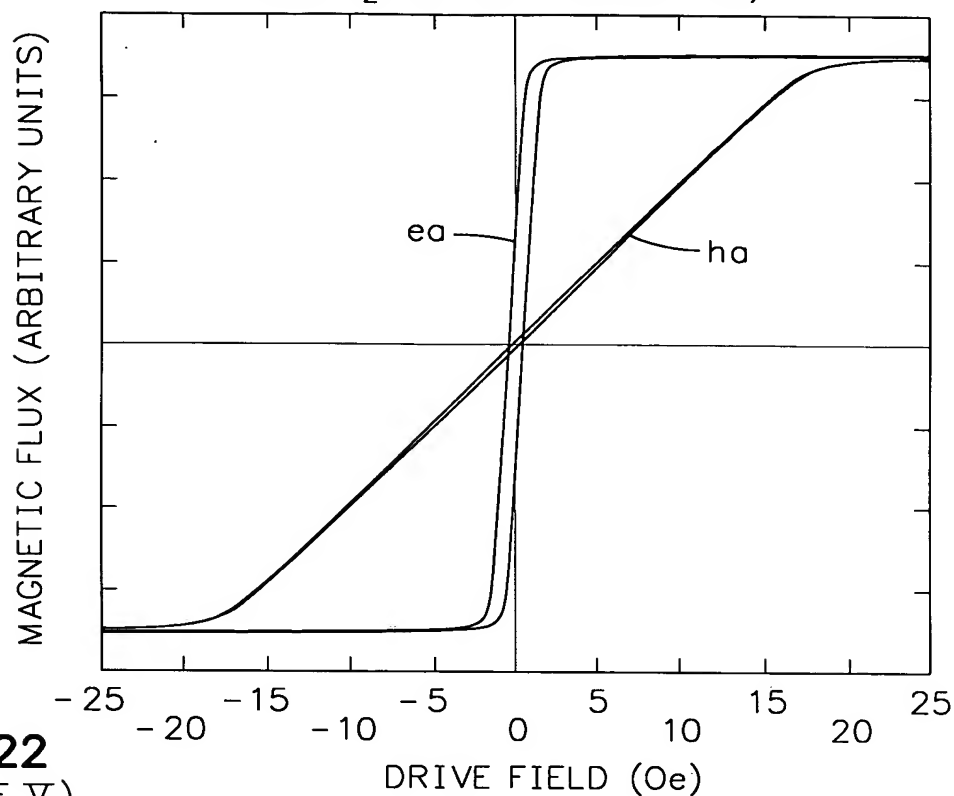


FIG. 22
(EXAMPLE V)

25Å ALUMINA/1.80μm NiFeCo-O-N/25Å ALUMINA
(2.0% N₂O/Ar AS-DEPOSITED)

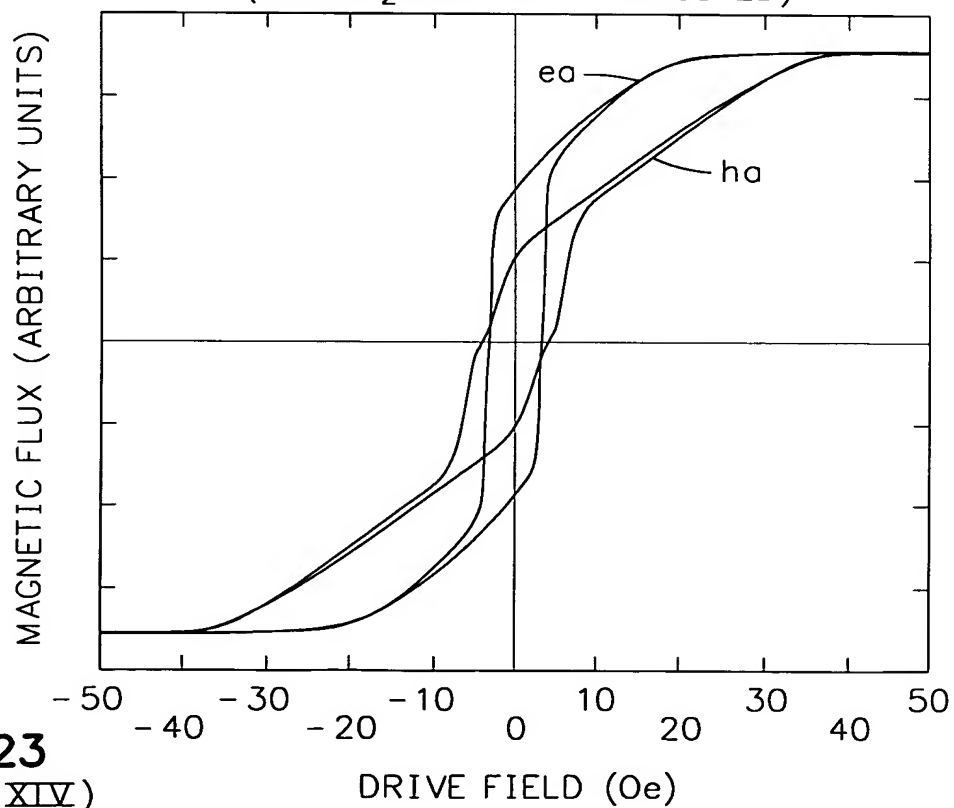


FIG. 23
(EXAMPLE XIV)

25Å ALUMINA/1.80 μ m NiFeCo-N/25Å ALUMINA
(2.0% N₂/Ar AS-DEPOSITED)

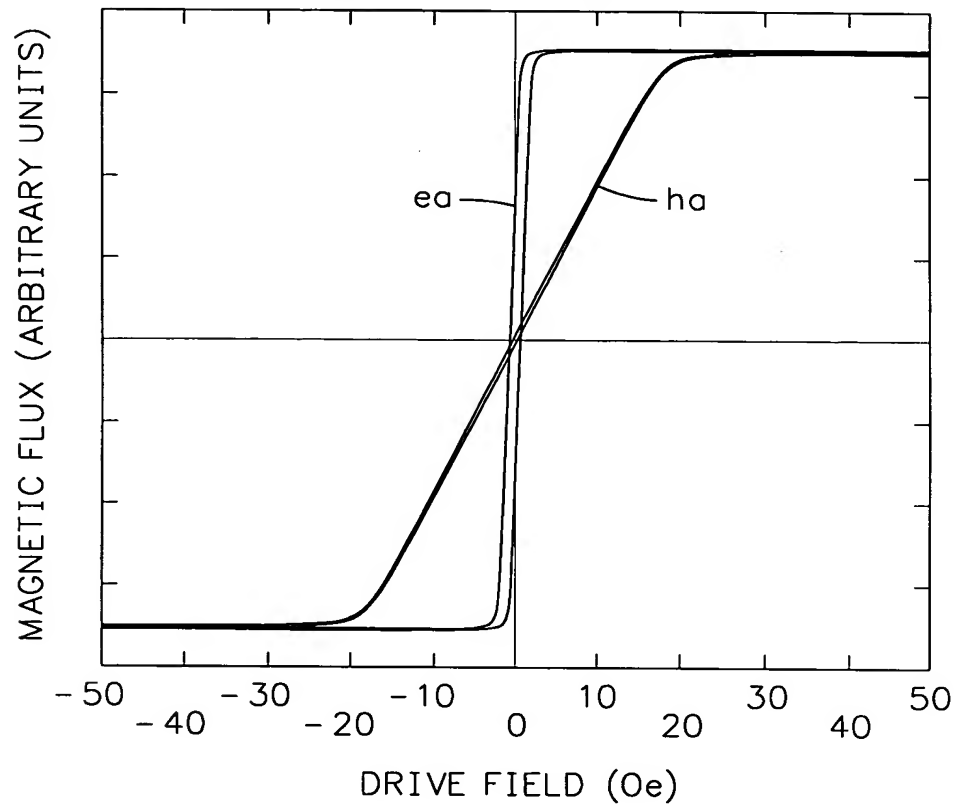
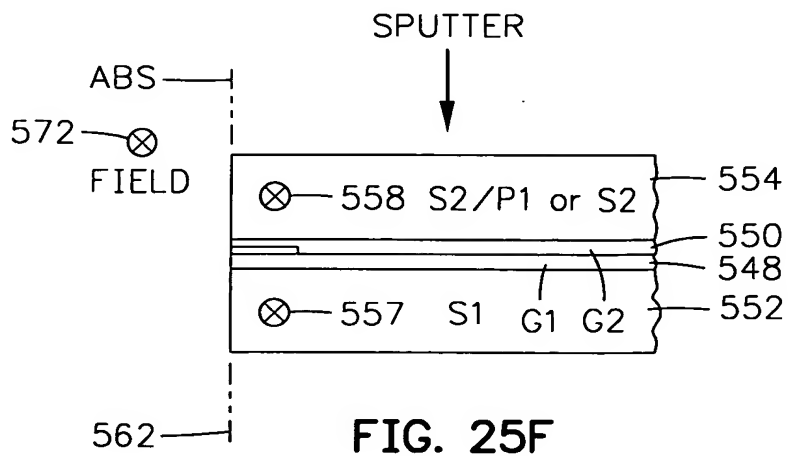
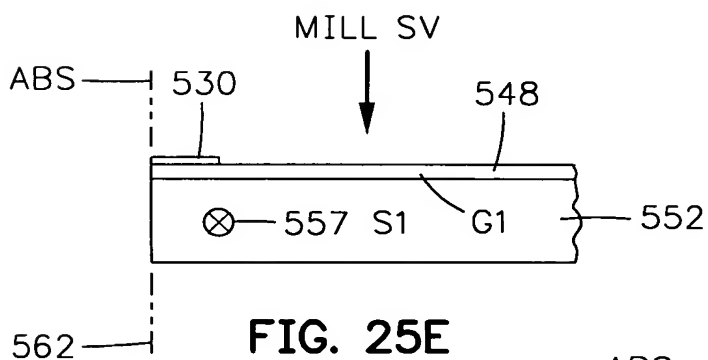
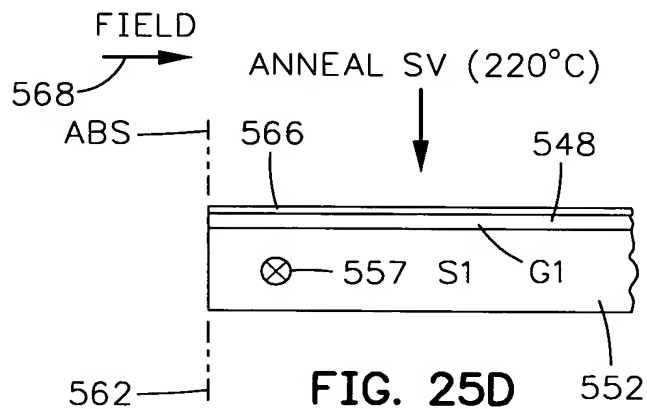
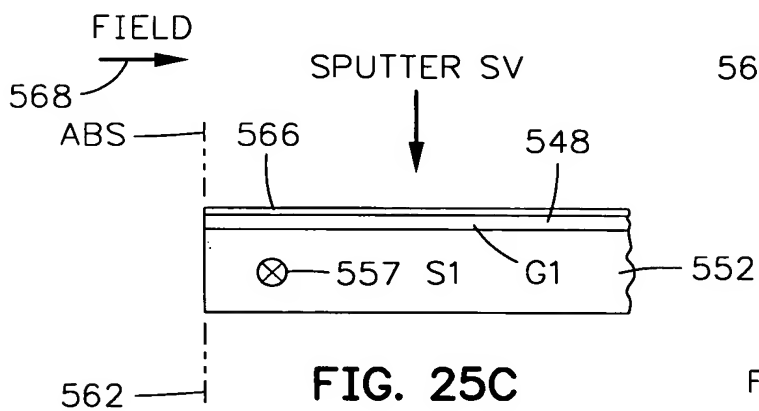
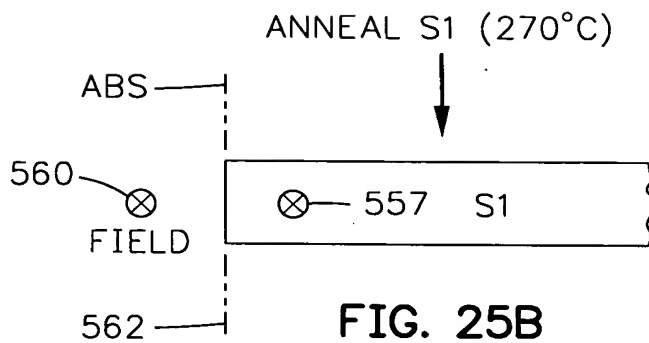
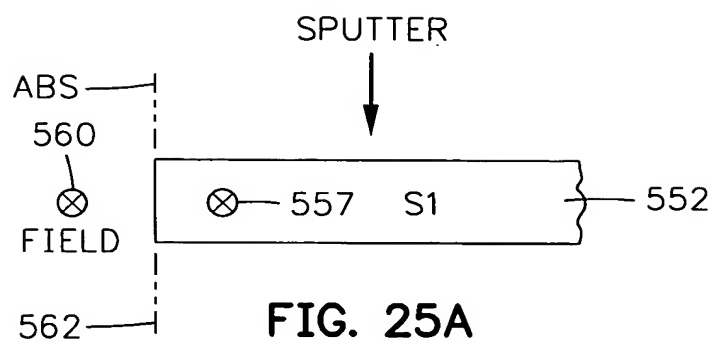
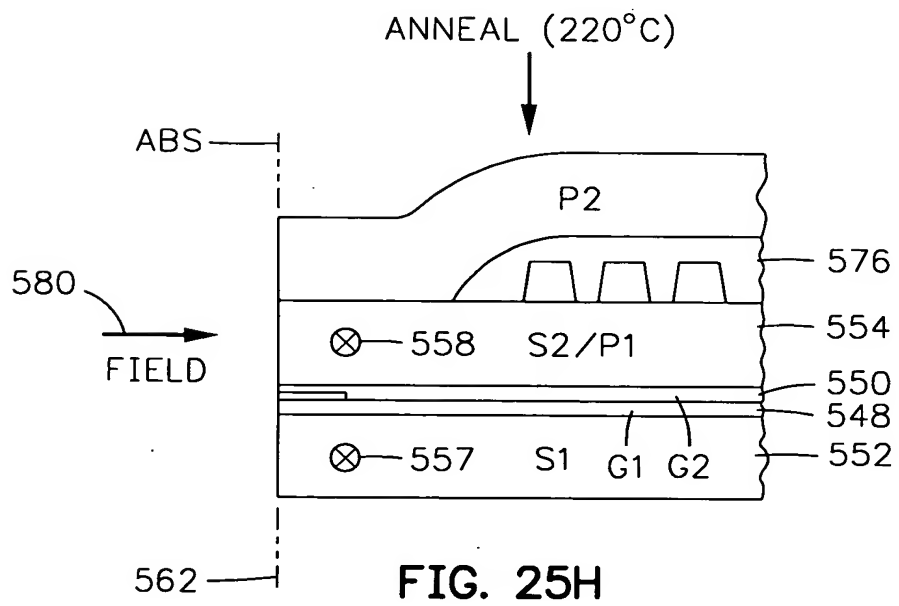
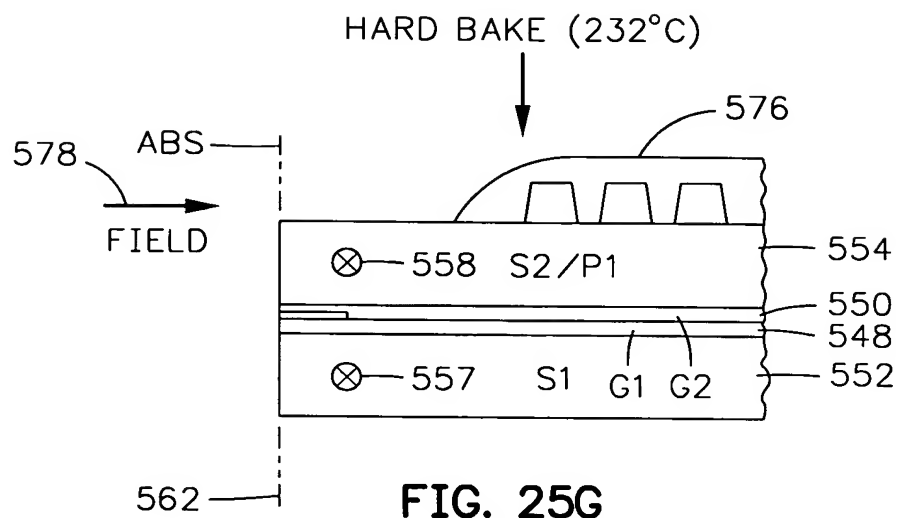


FIG. 24
(EXAMPLE XV)





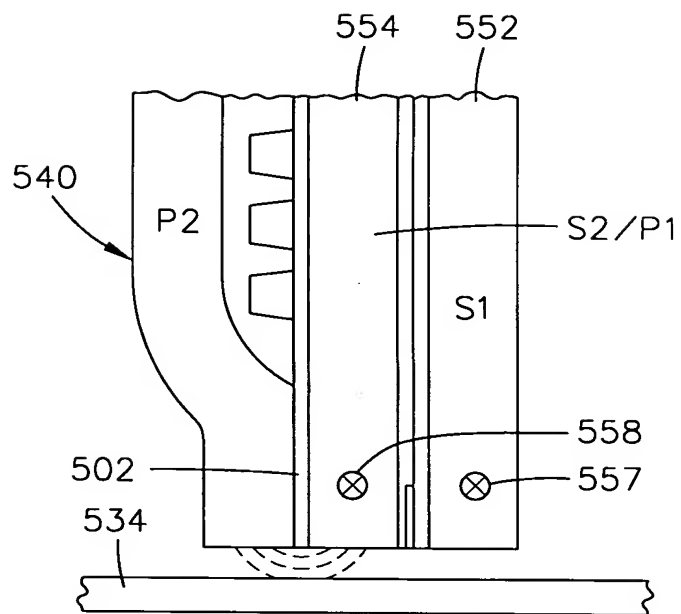


FIG. 26

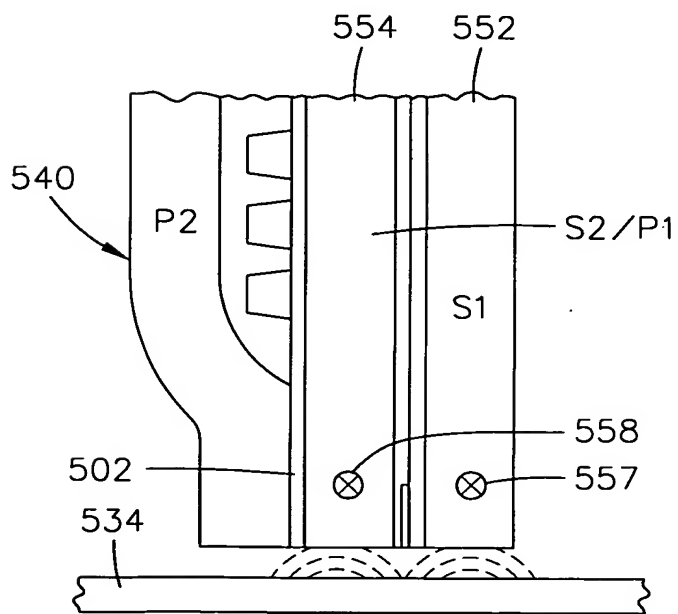


FIG. 27

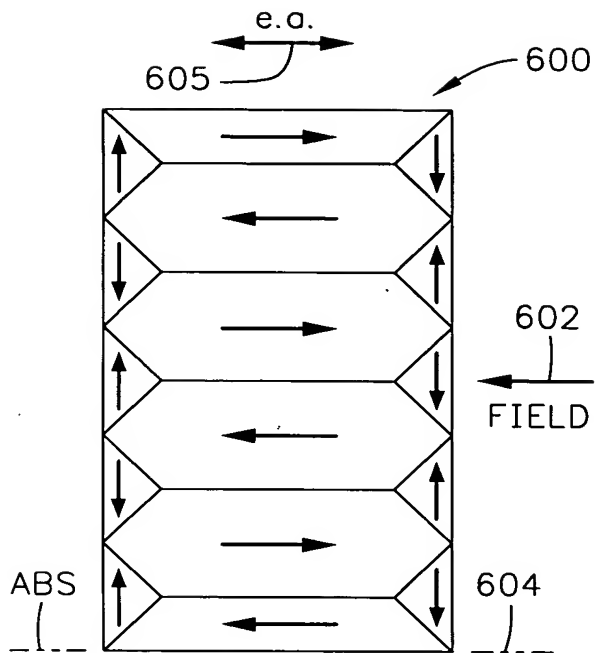


FIG. 28A
(PRIOR ART)

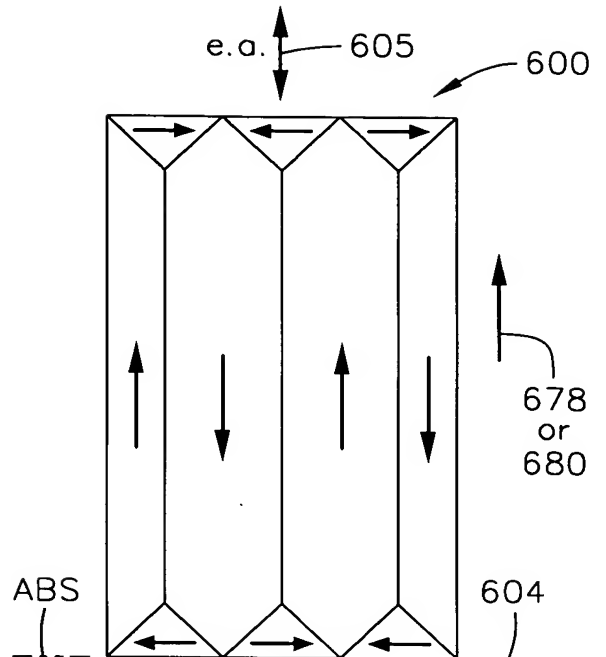


FIG. 28B
(PRIOR ART)

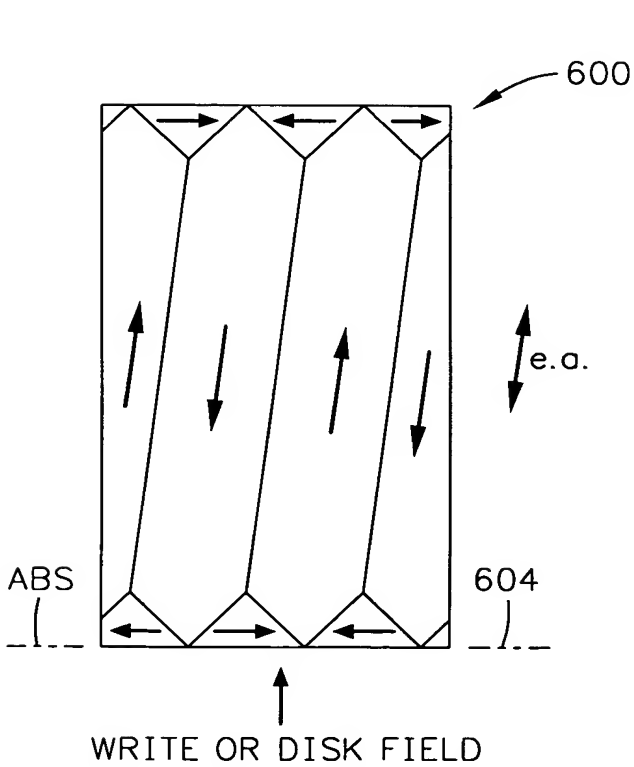


FIG. 28C
(PRIOR ART)

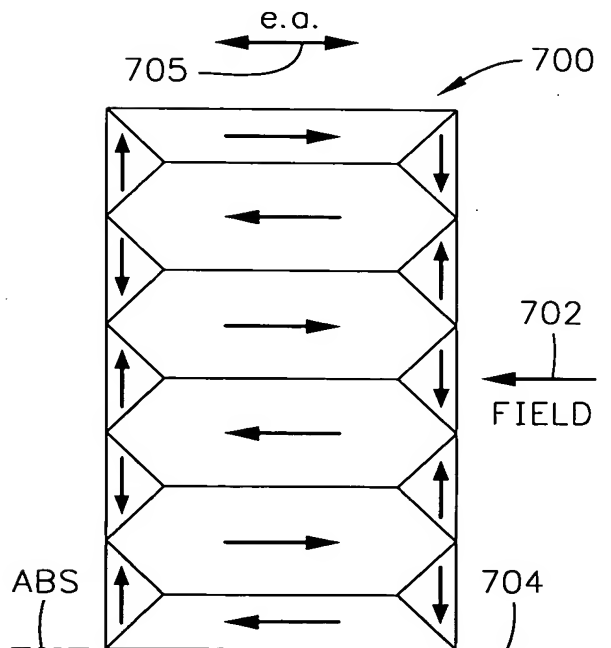


FIG. 29A

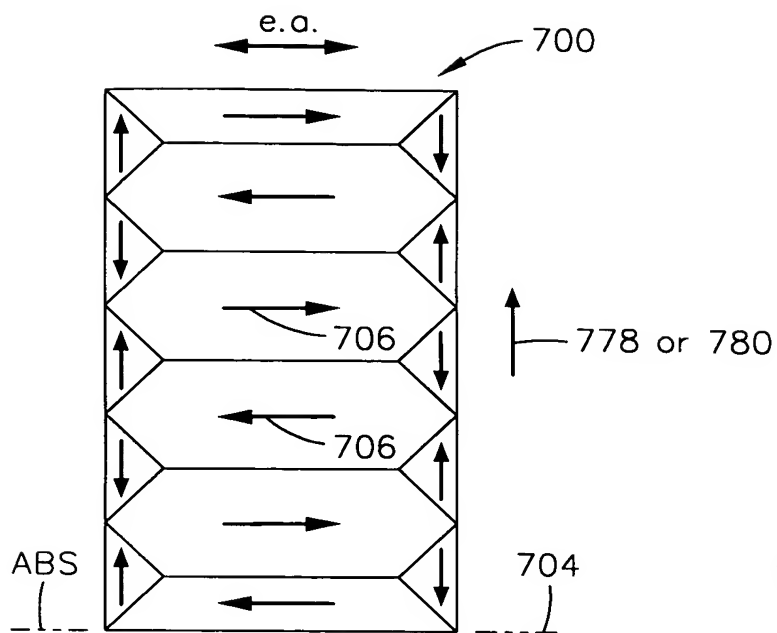


FIG. 29B

NiFeCo [-O] - N AFTER HARDBAKE
ANNEALING OR RESETTNG
IN THE PRESENCE OF A FIELD
PERPENDICULAR TO THE ABS

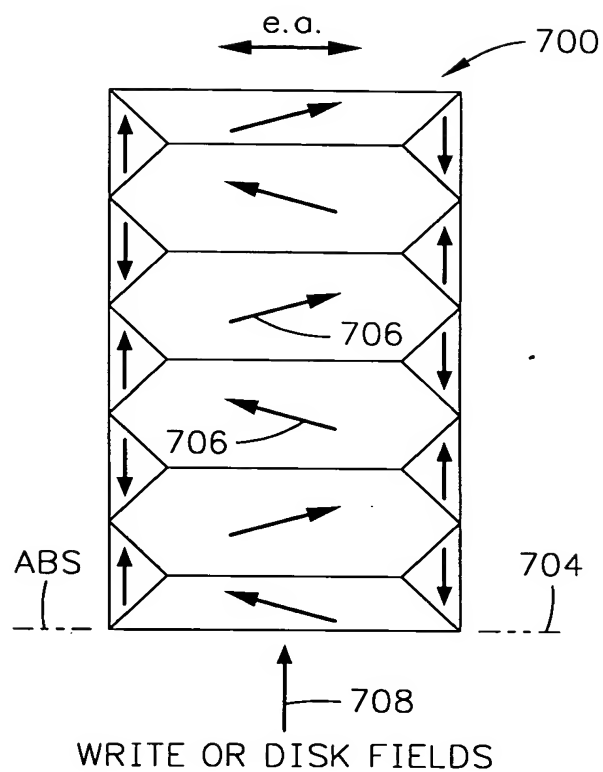


FIG. 29C

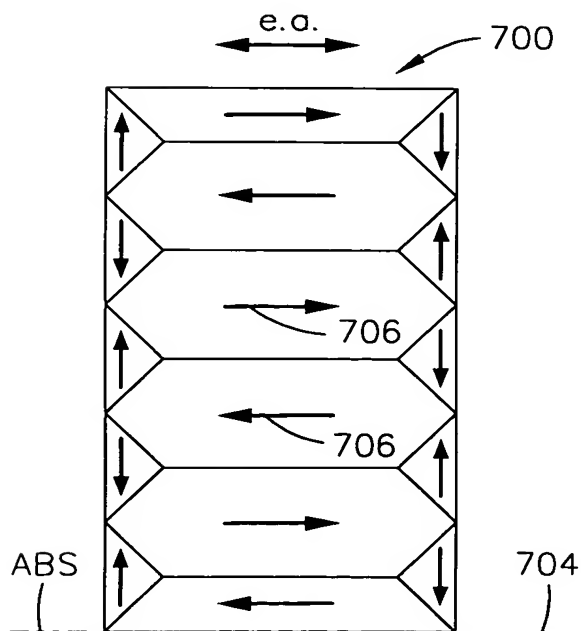


FIG. 29D